	Туре	L#	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition
1	BRS	L1	905	(cmp or ((chemical\$2 mechanical\$2) adj (polish\$3 or planariz\$5)) or polish\$3 or planariz\$5) same ((first and second) adj4 (abrasive or slurry))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/09/02 18:53	•	
2	BRS	L2	337	(cmp or ((chemical\$2 mechanical\$2) adj (polish\$3 or planariz\$5)) or polish\$3 or planariz\$5) same ((first and second) adj4 (abrasive or slurry)) same (wafer or semiconductor)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/09/02 19:15		·
3	BRS	L3	78	2 and @pd<="20010830"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/09/02 19:19		
4	BRS	L4	50	(cmp or ((chemical\$2 mechanical\$2) adj (polish\$3 or planariz\$5)) or polish\$3 or planariz\$5) same (((first and second) adj4 (abrasive or slurry or polish\$3)) same (organic or alcohol or acetone or \$4nol)) same (wafer or semiconductor)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/09/02 19:59		
5	BRS	L5	11	4 and @pd<="20010830"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/09/02 19:49		
6	BRS	L6	39	4 not 5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/09/02 19:28		

	Туре	L#	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition
7	BRS	L7	52	second) adj4 (abrasive or slurry	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/09/02 20:04		
8	BRS	L8	52	(cmp or ((chemical\$2 mechanical\$2) adj (polish\$3 or planariz\$5)) or polish\$3 or planariz\$5) same (((first and second) adj4 (abrasive or slurry or polish\$3)) same (organic or alcohol or acetone or methanol or ethanol or isopropanol or "isopropyl alcohol" or \$4nol)) same (wafer or semiconductor)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/09/02 19:48		
9	BRS	L9	13	8 and @pd<="20010830"	, ,	2005/09/02 20:00		
10	BRS	L10	85	planariz\$5)) or polish\$3 or planariz\$5) same (((first and second) adj4 (abrasive or slurry or polish\$3)) same (organic or	,	2005/09/02 20:23		
11	BRS	L11	19	10 and @pd<="20010830"		2005/09/02 20:06		

	Туре	L#	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition
12	BRS	L12	0	(cmp or ((chemical\$2 mechanical\$2) adj (polish\$3 or planariz\$5)) or polish\$3 or planariz\$5) same (((first and second) adj4 (abrasive or slurry or polish\$3)) same (nonaqueous)) same (wafer or semiconductor)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/09/02 20:05		
13	BRS	L13	0	(cmp or ((chemical\$2 mechanical\$2) adj (polish\$3 or planariz\$5)) or polish\$3 or planariz\$5) same (((first and second) adj4 (abrasive or slurry or polish\$3)) same (nonpolar or polar)) same (wafer or semiconductor)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/09/02 20:05		
14	BRS	L14	63	(cmp or ((chemical\$2 mechanical\$2) adj (polish\$3 or planariz\$5)) or polish\$3 or planariz\$5) same (((first and second) adj4 (abrasive or slurry or polish\$3)) same (solvent))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/09/02 20:06		
15	BRS	L15	25	14 and @pd<="20010830"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/09/02 20:24		
16	BRS	L16	163	(cmp or ((chemical\$2 mechanical\$2) adj (polish\$3 or planariz\$5)) or polish\$3 or planariz\$5) same (((first and second) adj7 (abrasive or slurry or polish\$3)) same (organic or alcohol or acetone or \$4nol or solvent or medium or media or dispers\$3)) same (wafer or semiconductor)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/09/02 20:23		
17	BRS	L17	37	16 and @pd<="20010830"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2005/09/02 20:24		

	Туре	L#	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition
18	BRS	L18	29	17 not 15		2005/09/02 20:24		